

INFORMATION DISCLOSURE
STATEMENT BY APPLICANT

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MAR 31 2013

Complete if Known

Application Number	09/701,065
Filing Date	February 12, 2001
First Named Inventor:	Fabrice Geiger
Group Art Unit	1756
Examiner Name	Duda, Kathleen
Attorney Docket Number	2013 USA P/DSM/PMD/JW

Sheet

1

of

2

Attorney Docket Number 2013 USA P/DSM/PMD/JW

U.S. PATENT DOCUMENTS

[illegible]

FOREIGN PATENT DOCUMENTS

Exam. Initial*	C i t e n o. 1	Foreign Patent Document			Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM- DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	Translation? Yes/No
		Office ³	Number ⁴	Kind Code ⁵ (If known)				
		DE	195 28 746	C1	Grassl, Thomas et al.	10-31-1996		No
KWD		EP	0 843 348	A2	Li-Qun, Xia et al.	05-20-1998		Yes

Examiner
Signature

K. Duda

Date Considered
5-19-02

***EXAMINER:** Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹Unique citation designation number. ²See attached Kinds of U.S. Patent Documents. ³Enter Office that issued the document, by the two-letter code (WIPO Standard S.3). ⁴For Japanese patent documents, the indication of the year of reign of the Emperor must precede the serial number of the patent document. ⁵Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.16 if possible. ⁶Applicant is to place a check mark here if English language Translation is attached.

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Substitut f r Form 1449A/PTO (Modified) INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary) <div style="border: 1px solid black; border-radius: 50%; padding: 5px; display: inline-block; transform: rotate(-15deg);"> MAR 31 2003 TRADEMARK OFFICE 8 </div>		Complete if Known <table border="1" style="width: 100%; border-collapse: collapse;"> <tr> <td style="width: 50%;">Application Number</td> <td>09/701,065</td> </tr> <tr> <td>Filing Date</td> <td>February 12, 2001</td> </tr> <tr> <td>First Named Inventor:</td> <td>Fabrice Geiger</td> </tr> <tr> <td>Group Art Unit</td> <td>1756</td> </tr> <tr> <td>Examiner Name</td> <td>Duda, Kathleen</td> </tr> <tr> <td>Attorney Docket Number</td> <td>2013 USA P/DSM/PMD/JW</td> </tr> </table>		Application Number	09/701,065	Filing Date	February 12, 2001	First Named Inventor:	Fabrice Geiger	Group Art Unit	1756	Examiner Name	Duda, Kathleen	Attorney Docket Number	2013 USA P/DSM/PMD/JW
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Sheet	2	of	2												
OTHER ART – NO PATENT LITERATURE DOCUMENTS															
Examiner Initials*	Cite No ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published			T ²										
KUD		ELBEL, NORBERT, ET AL., A New STI Process Based on Selective Oxide Deposition; 1998 Symposium on VLSI Technology Digest of Technical Papers, (CAT NO. 98CH36216), Honolulu, USA, June 9-11, 1998, pages 208-209, XP000802805, 1998, New York, NY, USA, IEEE, ISBN: 0-7803-4770-6/98 © 1998 IEEE.													
KUD		FISCHER, E., ET AL., Global Planarization By Selective Deposition Of Ozone/TEOS, 1995 VMIC Conference, June 27-29, 1995, pages 247-253, XP002109501.													
KUD		LEE, HAN SIN, ET AL., An Optimized Densification of the Filled Oxide for Quarter Micron Shallow Trench Isolation (STI), 1996 Symposium On VLSI Technology, Digest Of Technical Papers, Honolulu, USA, June 11-13, 1996, pages 158-159, XP000639314, Institute Of Electrical And Electronics Engineers, ISBN: 0-7803-3342-X/96 © 1996 IEEE.													
KUD		Patent Abstracts Of Japan, Vol. 015, No. 464 (E-1137), November 25, 1991, and JP 03 198339 A (Maeda Kazuo et al.) August 29, 1991, pages 211-215.													
KUD		Search Report for PCT/IB 99/00835, mailed November 26, 1999, 7 pages.													

Examiner Signature	K. Duda	Date Considered	5-19-03
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